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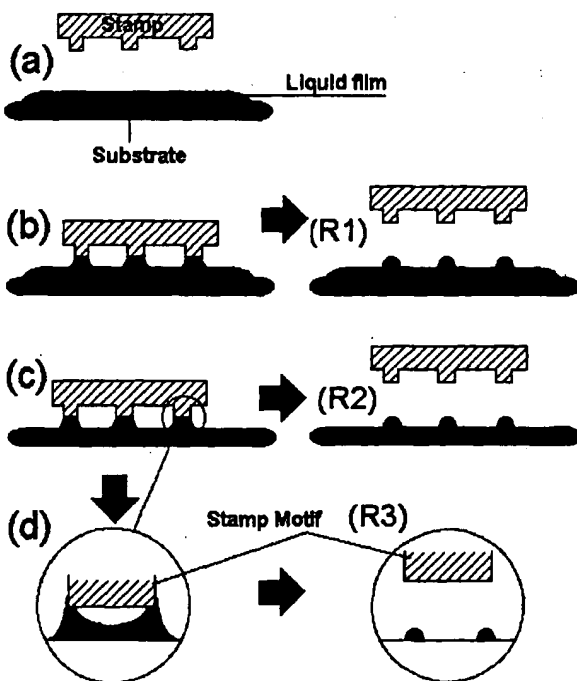
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(54) Title: METHOD FOR MANUFACTURING AND CONTROLLING STRUCTURES AND PATTERNS OF SOLUBLE AND COLLOIDAL SUBSTANCES BY PRINTING ON THE MICROMETER AND NANOMETER SCALE AND WITH REDUCTION OF THE DIMENSIONS OF THE STAMP'S FEATURES



(57) Abstract: A printing process for obtaining patterns of nanometer and micrometer dimensions on a substrate, comprising i) the application of a solution or suspension of an imprinting material to the substrate, ii) the positioning, without applying pressure, of a stamp provided with relief patterns at a distance of 0 nm to 500 μ m from the substrate, and iii) the evaporation of the solution or suspension.

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